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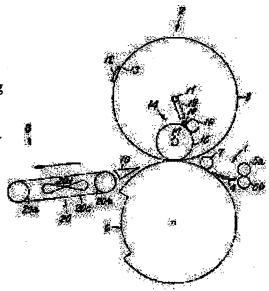
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## (54) O/W TYPE EMULSION INK FOR STENCIL PRINTING AND PRINTING METHOD USING THE INK

## (57) Abstract:

PROBLEM TO BE SOLVED: To provide an O/W type emulsion ink for a stencil printing and a stencil printing method, with an excellent fixing property to a substance to be printed, capable of imparting a clear print image having no blur and offset.

SOLUTION: The O/W type emulsion ink for a stencil printing is provided, which is characterized that at least one or more kinds of carbon nanotube is contained in an oil phase and/or an aqueous phase in the O/W type emulsion ink constituted by the oil phase of 10-90% by weight and the aqueous phase of 90-10% by weight. The stencil printing method is provided, which comprises including a step for boring a heat-sensitive stencil sheet by a thermal head or a laser beam having a heating action; a step for setting the bored sheet onto a stencil printing body; a step for passing the O/W emulsion ink through the bored part of the sheet; and a step for transferring the passed ink onto a printing paper by a magnetic field.



## LEGAL STATUS

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